

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	4002	mask\$3 and pattern\$1 and correct\$3 and wafer\$1 and optical and project\$3	USPAT	2004/03/05 08:41
2	BRS	L2	152	1 and (adjacent or near\$3 or negibor\$3) adj pattern\$1	USPAT	2004/03/05 08:42
3	BRS	L3	137	2 and (distance or length)	USPAT	2004/03/05 08:43
4	BRS	L4	40	3 and design near2 pattern	USPAT	2004/03/05 08:43
5	BRS	L5	25	4 and rule\$1	USPAT	2004/03/05 08:44
6	BRS	L6	14	5 and edge\$1	USPAT	2004/03/05 08:44

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1	BRS	L1	4002	mask\$3 and pattern\$1 and correct\$3 and wafer\$1 and optical and project\$3	USPAT	2004/03/05 08:41
2	BRS	L2	152	1 and (adjacent or near\$3 or negibor\$3) adj pattern\$1	USPAT	2004/03/05 08:42
3	BRS	L3	137	2 and (distance or length)	USPAT	2004/03/05 08:43
4	BRS	L4	40	3 and design near2 pattern	USPAT	2004/03/05 08:43
5	BRS	L5	25	4 and rule\$1	USPAT	2004/03/05 08:44
6	BRS	L6	14	5 and edge\$1	USPAT	2004/03/05 08:58
7	BRS	L7	9	6 and simulation	USPAT	2004/03/05 08:58
8	BRS	L8	8	7 and intensity	USPAT	2004/03/05 08:58
9	BRS	L9	8	8 and size	USPAT	2004/03/05 08:59
10	BRS	L10	8	9 and design near pattern	USPAT	2004/03/05 08:59
11	BRS	L11	5	10 and target	USPAT	2004/03/05 08:59
12	BRS	L12	2	11 and critical	USPAT	2004/03/05 09:00